

Fig. 1 HfO<sub>2</sub> and SiO<sub>2</sub> thicknesses as a function of ALD cycle by ALD at 300 °C using H<sub>2</sub>O gas and TDMAHf and TDMAS, respectively.

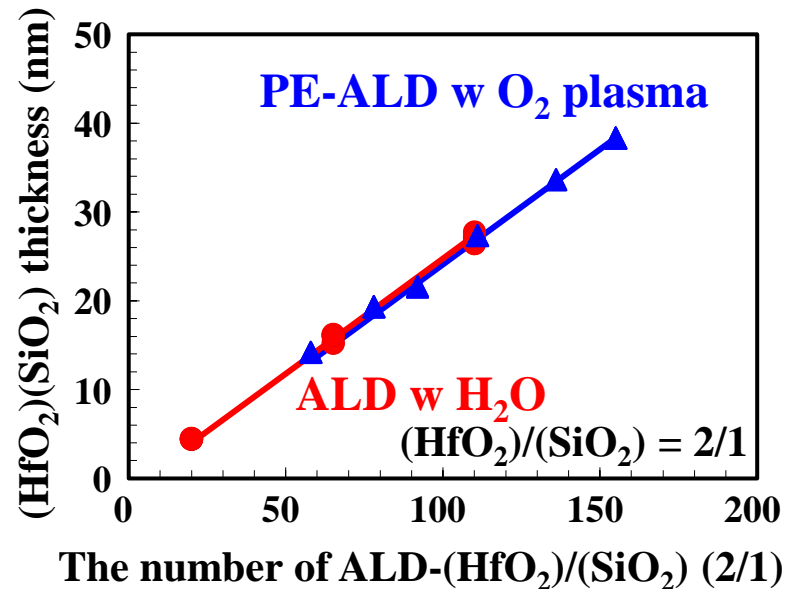


Fig. 2 (HfO<sub>2</sub>)/(SiO<sub>2</sub>) (2/1) nanolaminate thicknesses as a function of ALD cycle by ALD with H<sub>2</sub>O and PE-ALD with O<sub>2</sub> plasma at 300 °C.